SUBSTRATE MENISCUS INTERFACE AND METHODS FOR OPERATION

ABSTRACT OF THE DISCLOSURE

An apparatus for processing a substrate with a fluid meniscus to be applied to a surface of the substrate is provided which includes a docking surface configured to be placed adjacent to an edge of the substrate where the docking surface is in the same plane as the substrate. The docking surface provides a transition interface to allow the fluid meniscus to enter and exit the surface of the substrate.

(Fig. 2A)